

Please type a plus sign (+) inside this box 

Approved for use through 10/31/2002. OMB 0651-0031

Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB control number.

Substitute for Form 1449A/PTO

**INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet	1	of	1	Attorney Docket No.	TI-34962.1
-------	---	----	---	---------------------	------------

**Complete If Known**

Application Number	TBD
Filing Date	Herewith
First Named Inventor	William W. Dostalik
Group Art Unit	2814
Examiner Name	Howard Weiss

**U.S. PATENT DOCUMENTS**

Exam. Initials*	Cite No. <sup>1</sup>	U.S. Patent Document		Name of Patentee or Applicant of Cited Doc.	Date of Pub. of Cited Doc. (mm-dd-yyyy)	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code <sup>2</sup> (if known)			
AA	6,319,809			Chang et al.	11/20/01	
AB	6,372,647			Lu et al.	4/16/02	
AC						
AD						
AE						
AF						
AG						
AH						
AI						
AJ						
AK						
AL						

**FOREIGN PATENT DOCUMENTS**

Exam. Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Name of Patentee or Applicant of Cited Doc.	Date of Pub. of Cited Doc. (mm-dd-yyyy)	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Office <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>2</sup> (if known)				
BA								
BB								
BC								
BD								
BE								
BF								
BG								

**OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS**

Exam. Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	CA	U.S. Patent Application Publication No. 2002/0081855, June 27, 200, Jiang et al.	
	CB	S. SATYANARAYANA ET AL., "A Solution to Resist Poisoning in the Integration of 248 and 193 nm Photoresist with Low-k Dielectric Materials" Society of Photo-Optical Instrumentation Engineers, Santa Clara, California, March 2002	
	CC		
	CD		
	CE		
	CF		
	CG		

Examiner Signature	Date Considered
--------------------	-----------------

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

**US and Foreign Patent Documents:** <sup>1</sup>Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

**Other Prior Art/Non-Patent Literature Documents:** <sup>1</sup>Unique citation designation number. <sup>2</sup>Applicant is to place a check mark here if English Translation is attached.